

Transparent Oxides for Electronics: problem of electrical transport

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OXIDES: Transparent & Conducting

Heat reflecting windows, electrochromic windows, LCD panel, OLED, solar cells, touch panels ,.....

Advantage of oxides:

- ✓ Higher voltage tolerances;
- ✓ More stability at high temperatures;
- ✓ Oxygen tolerance, opening up gas and air monitoring applications;
- ✓ The ability to make transparent electronics
- ✓ Magnetic sensors

Expect market value for TCOs in coming years will be more than 200 billions \$



Goodbye silicon, hello oxides!!!



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Figure of Merit for TCO

The first TCO by J.M.MOCHEL, *U.S. PATENT NO.2,564, (1947) 706*

$$\frac{\sigma}{\alpha} = -\{R_s \ln(T+R)\}^{-1}$$

Electrical Conductivity

Optical absorption

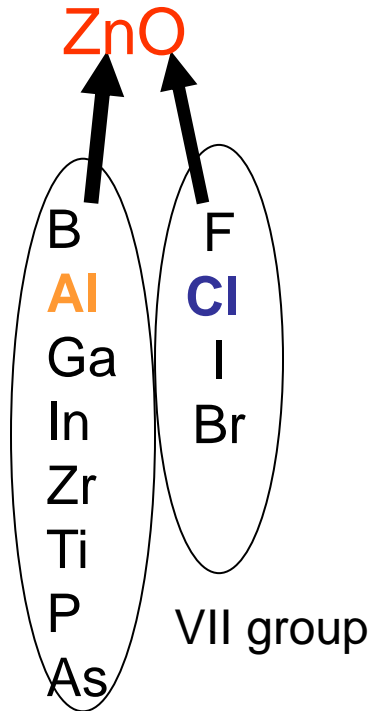
R.Gordon MRS Bull.2000

n type TCO

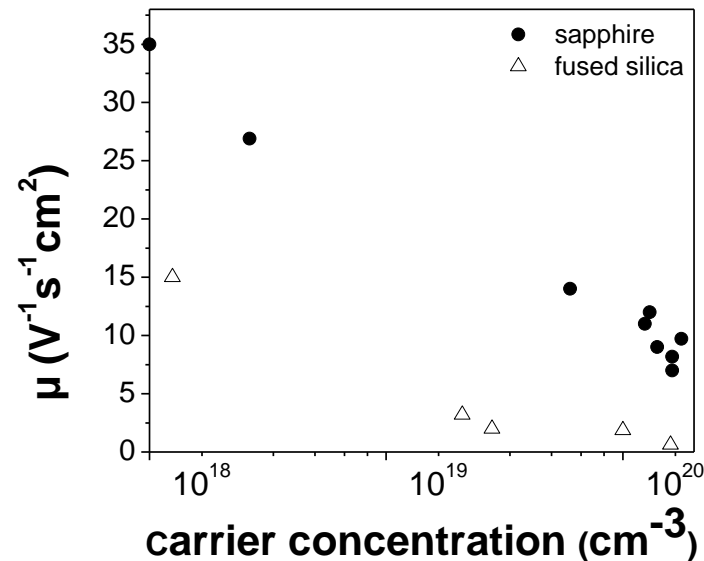
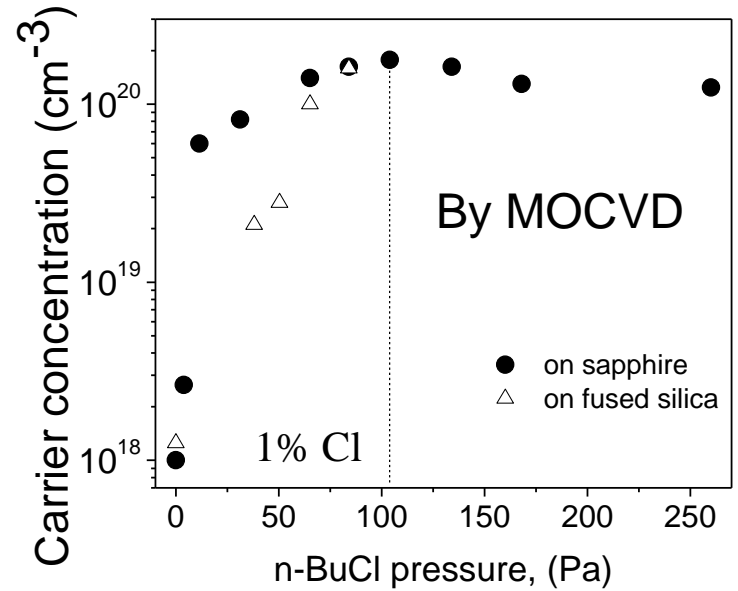
Important criteria for TCO:

➤ The cost of the raw materials →
 Cd < **Zn** < Ti < Sn < Ag < ~~In~~

➤ Toxicity of the elements →
Zn < Sn < In < Ag < Cd
 R.Gordon, MRS Bull. 2000



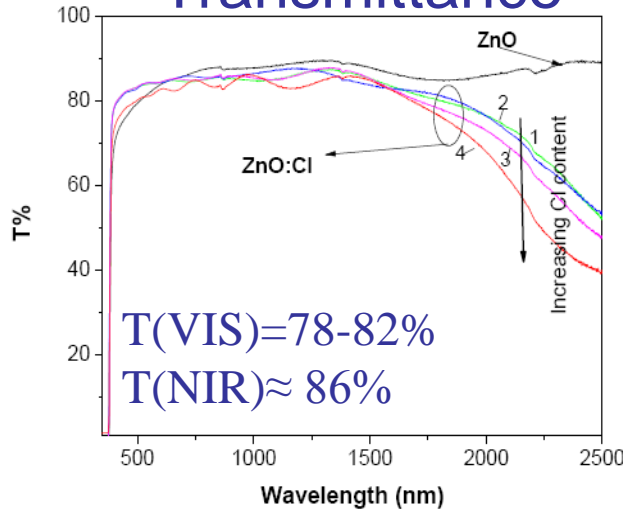
ZnO:Cl



Phys. stat. sol. (a) **203**, 2007

n type TCO

Transmittance

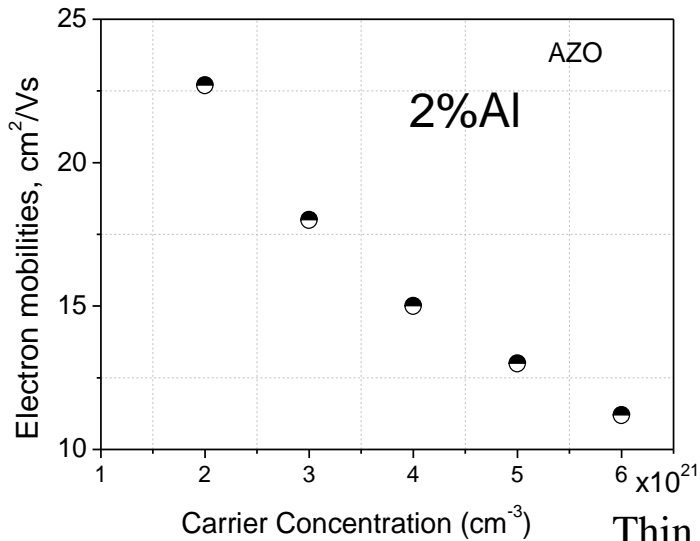


ZnO:Cl

$$\rho = 1.3 \times 10^{-3} \text{ Ohm cm}$$

$$n = 6.1 \times 10^{20} \text{ cm}^{-3}$$

$$\mu = 7 \text{ cm}^2/\text{Vs}$$

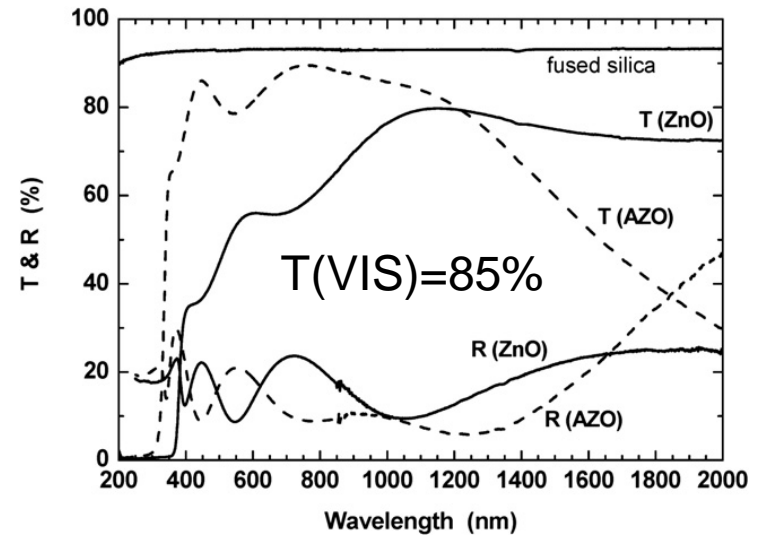


AZO by PLD

$$\rho = 1.2 \times 10^{-4} \text{ Ohm cm}$$

$$n = 1.2 \times 10^{21} \text{ cm}^{-3}$$

$$\mu = 18 \text{ cm}^2/\text{VS}$$



p type TCO

WBG metal-oxydes

Most are **Insulators** ; Few are naturally **n-type**; rarely naturally **p-type**

The monopolarity in existing TCOs results from strong localization of positive holes at oxygen 2p levels or an upper edge of the valence band due to the strong electronegative nature of oxygen.

➤ Conductivity type inversion in n-type TCO by cation doping

SnO₂, CdO, ZnO, In₂O₃....

Difficulty (solubility limit, killer defects, deep levels)

➤ « Chemical modulation of VB »

Delocalize holes by reduction of Columb interaction

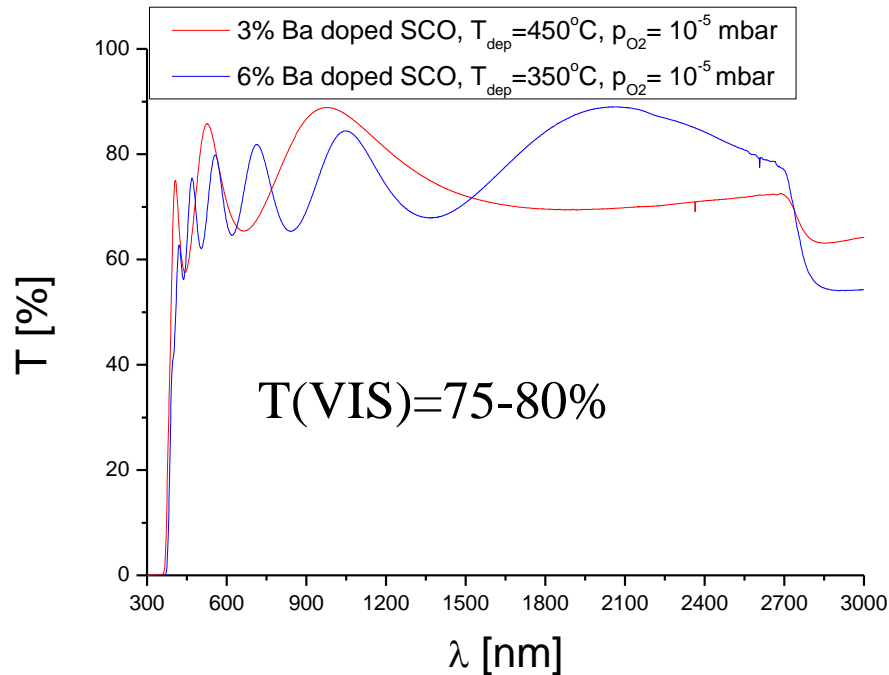
delafossites : CuAlO₂, (Kawazoe et al, 1997)

CuGaO₂; CuInO₂; CuCrO₂; CuBO₂;

Problem: very high deposition T, indirect band gap

Transparent p-n junction: *oxide with direct band gap, low deposition T, high quality epi-layers*

Cu based p type TCO



Cu_2O (archetype of Cu based TCO)

V.B. Hybridised Cu 3d & O2p



localized holes



Polaronic-hopping conduction

(R.S.Toth, *Phys.Rev.* 122,482, 1961;

L.C.Bourne, *PRB* 40,10973, 1989)

Delocalization of holes

V_{Cu}

3d¹⁰Cu(I)

3d⁹Cu(II)

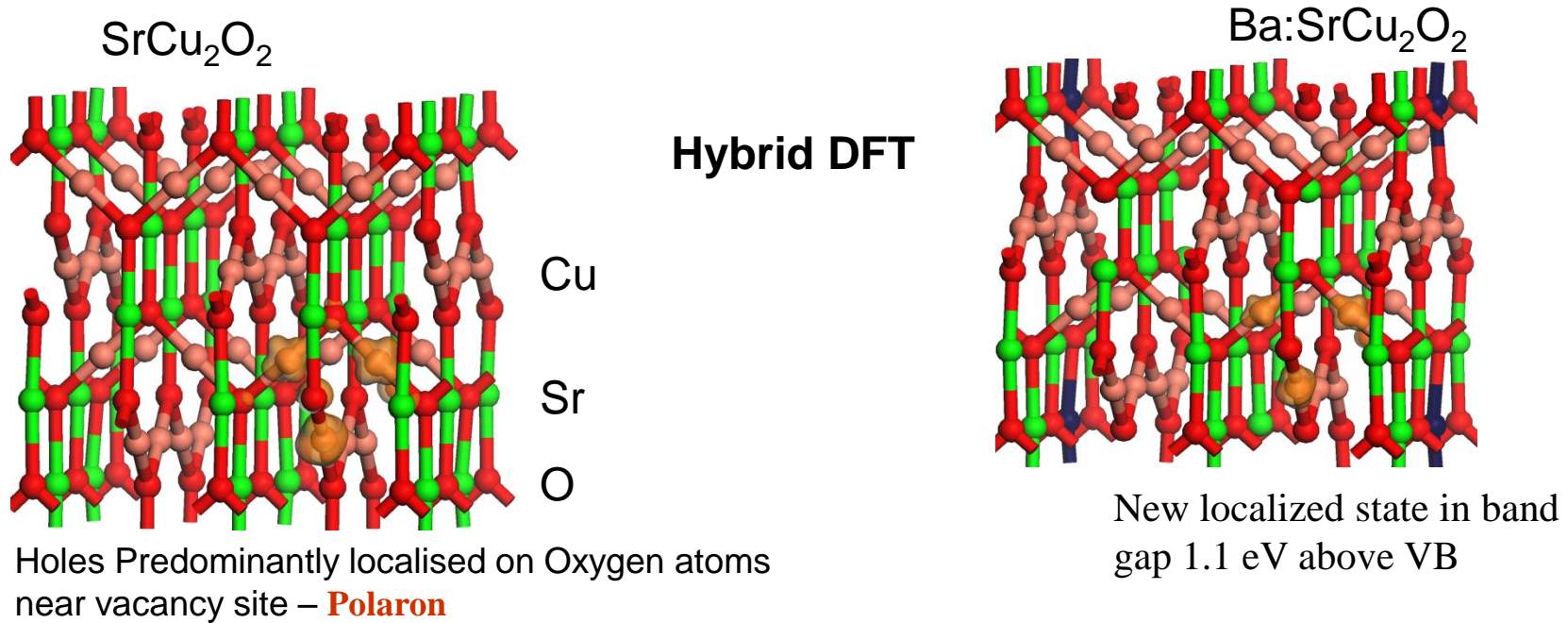
Coll: Tyndall National Institute University College Cork, Ireland;
Thales TRT, France

D.O.Scanlon, *PRL*, 103,096405, 2009
K.G.Godhino, *J.Matt.Chem.*20,1086,2010



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Introducing holes in $SrCu_2O_2$ by Ba doping



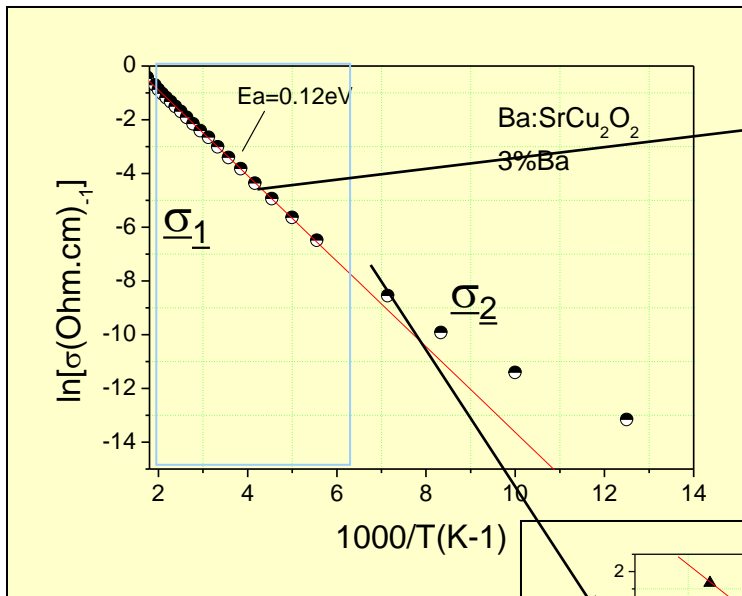
Structure	E_g / HSE06
$SrCu_2O_2$	3.20 eV
$Ba-SrCu_2O_2$	3.24 eV

Ba changes band gap but not the polaronic nature of the material

M.Nolan

Tyndall National Institute, University College Cork, Ireland

Conduction Mechanism of Ba:SCO



$$\sigma = \sigma_1 + \sigma_2$$

NNH

$\sigma_1 = \sigma_0 \exp(-W_H/k_B T)$
Constant Activation energy

$$E_a = [E_a(p(T)); E_a(\mu(T))]$$

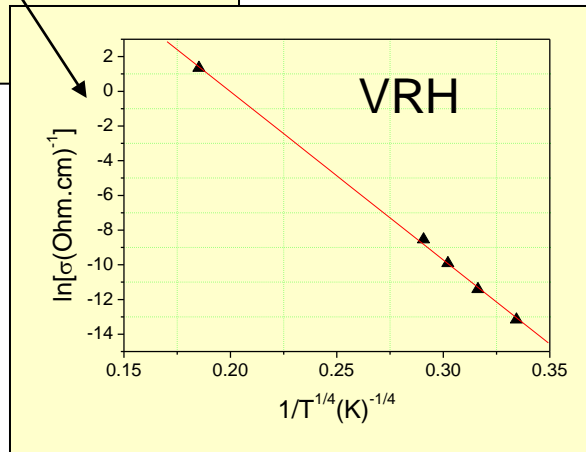
$E_a = E_a(\mu(T)) = W_H$ polaron hopping energy

$W_H = 120 \text{ meV}$

polaron binding energy $E_p = 240 \text{ eV}$

Polaron conductivity

@300K $\rho = 79 \text{ } \Omega \cdot \text{cm}$
 $\sigma = 1.2 \times 10^{-2} \text{ Scm}^{-1}$
 $p \sim 10^{17} \text{ cm}^{-3}$
 $\mu < 1 \text{ V}^{-1} \text{ s}^{-1} \text{ cm}^2$



$$\sigma_2 = \sigma_0 \exp(T_0/T)^{-1/4}$$

Activation energy

$$T_0 \sim \beta/k_{\text{NEF}} r p$$

$$T_0 = 9 \times 10^4 \text{ K}$$

Mobility is thermally activated



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Influence of Ba doping on Conductivity of SCO

%Ba	σ (S cm^{-1})	μ_H (cm^2/VS)	E_p eV Polaron binding energy
0	1×10^{-3}		
3	3×10^{-2}	<1	240
6	1.2×10^{-2}	<1	180

- Ba:SCO keeps good transparency in VIS (with small open of Gap)
- Ba doping induces less localised holes

Problem remains: low mobility of carriers

Delocalization of carriers by doping another dopant?

FTO- IR transparent conducting magnetic Oxide

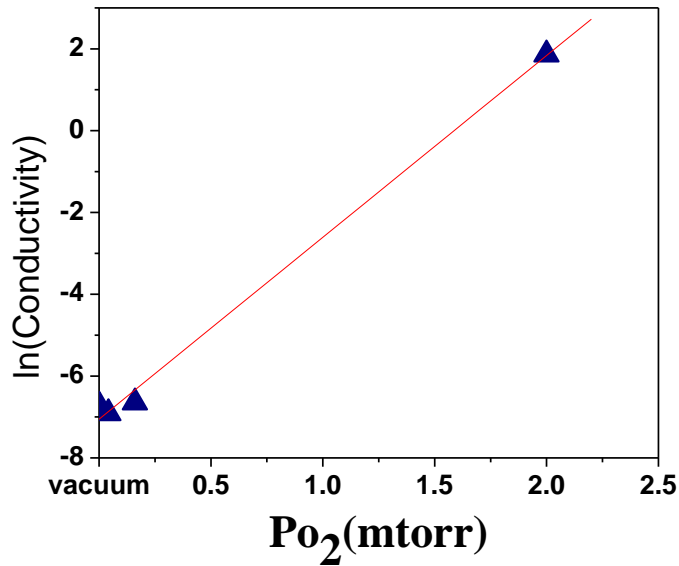
Ilmenite FeTiO_3

$E_g=3.5 \text{ eV}$

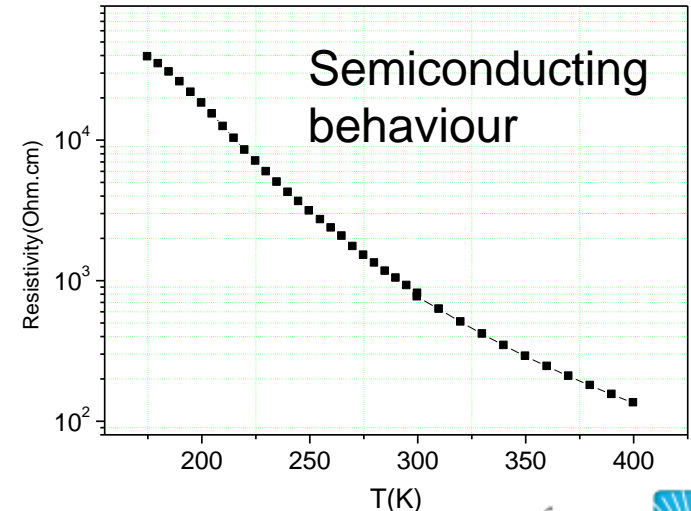
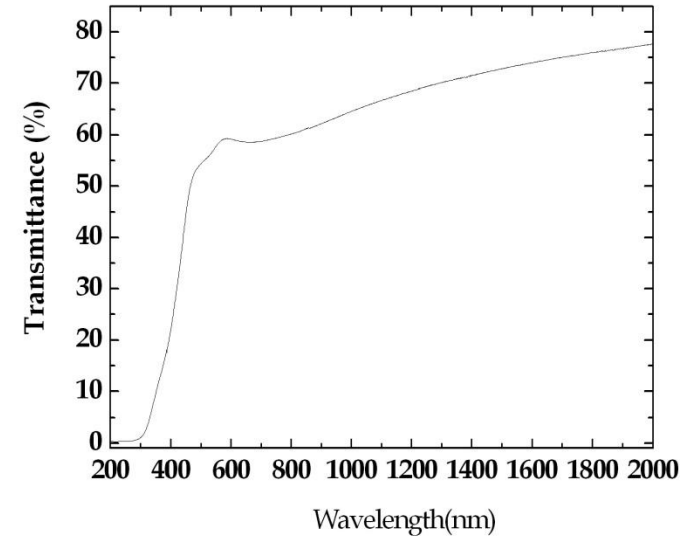
Antiferromagnet $T_N=55\text{K}$

By PLD

Growth $P_{\text{O}_2}=10^{-7} - 2 \text{ mTorr}$



p type conductivity



Conductivity increases with oxygen partial pressure



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Conductivity type inversion in FTO

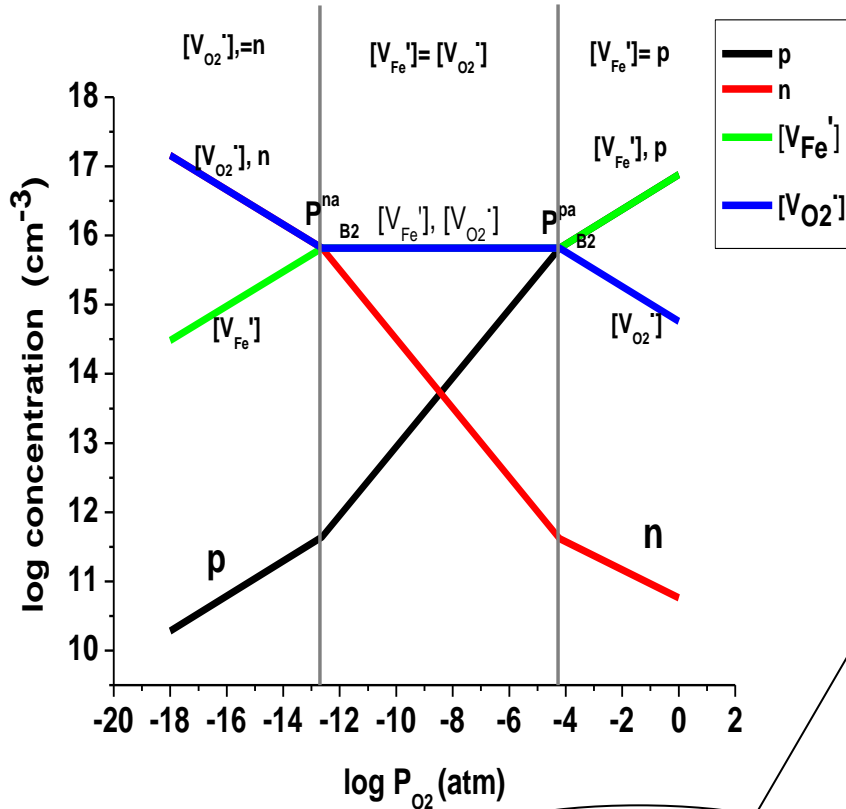
Thermodynamical analyses
n type insulator p type

Coll: T.Tchelidze, TSU, Georgia

Experiment:

Treatment in oxygen atmosphere

T=440°C



Hole conductivity $P_{O_2} > 6 \times 10^{-5} \text{ atm}$

Electron conductivity $P_{O_2} < 3 \times 10^{-13} \text{ atm}$

$P_{O_2} = 5.6 \times 10^{-4} \text{ atm}$	<i>p</i>
$P_{O_2} = 2 \times 10^{-13} \text{ atm}$	<i>n</i>

Conductivity type inversion



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Conclusion:

Present challenge is to get low temperature deposition of high quality p type type TCO.....

Future belongs to

“Invisible Electronics”

